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(54) **MASK CLEANING APPARATUS AND MASK CLEANING METHOD**

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(Continued)

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**ABSTRACT**

A mask cleaning apparatus and a mask cleaning method are provided. The mask cleaning method comprises: placing a mask (100) on a stage (20); and ejecting a dry ice particle group including a plurality of dry ice particles (101) toward a surface of the mask (100) at a speed of 340 m/s to 1000 m/s, within a cleaning time, wherein the plurality of dry ice particles (101) impact the surface of the mask (100) so as to remove a contaminant on the surface of the mask. Thereby, the mask cleaning apparatus and the mask cleaning method provided by embodiments of the present disclosure can remove the contaminant on the mask, without increasing a contamination medium and damaging the surface of the mask.

**20 Claims, 2 Drawing Sheets**

